



Freeform Search

for 10/825,871

Database:	US Pre-Grant Publication Full-Text Database
	US Patents Full-Text Database
	US OCR Full-Text Database
	EPO Abstracts Database
	JPO Abstracts Database
	Derwent World Patents Index
	IBM Technical Disclosure Bulletins

Term: 6367410 and (dome)  

Display: Documents in **Display Format:** Starting with Number

Generate: ☐ Hit List ☒ Hit Count ☐ Side by Side ☐ Image

Search

Clear

Interrupt

Search History

DATE: Saturday, November 19, 2005 [Printable Copy](#) [Create Case](#)Set Name Query

side by side

Hit Count Set Name

result set

DB=USPT; PLUR=YES; OP=ADJ

<u>L42</u>	6367410 and (dome)	1	<u>L42</u>
<u>L41</u>	6367410 and (plasma or rf)	2	<u>L41</u>
<u>L40</u>	6048798 and (flow)	7	<u>L40</u>
<u>L39</u>	6048798 and (sensor\$1 or controller\$1)	2	<u>L39</u>
<u>L38</u>	6048798 and (temperature)	14	<u>L38</u>
<u>L37</u>	6048798 and (target)	0	<u>L37</u>
<u>L36</u>	6048798 and (cda or air)	6	<u>L36</u>
<u>L35</u>	6048798 and (coolant)	0	<u>L35</u>
<u>L34</u>	6048798 and (heat adj exchanger)	0	<u>L34</u>
<u>L33</u>	6367410 and dome	1	<u>L33</u>
<u>L32</u>	6048798 and dome	0	<u>L32</u>

DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ

<u>L31</u>	L30 and (wafer or semiconductor)	48	<u>L31</u>
<u>L30</u>	((cda or air) near3 cool\$4) and (temperature near4 rf)	178	<u>L30</u>
<u>L29</u>	L28 and (wafer or semiconductor)	50	<u>L29</u>
<u>L28</u>	(cool\$3 near5 rf) same (cda or air)	191	<u>L28</u>

for
10/8 25, 871

<u>L27</u>	(cool\$3 near3 rf) same (cda or air)	132	<u>L27</u>
<u>L26</u>	(cool\$3 near3 rf)	1271	<u>L26</u>
<u>L25</u>	L24 and air	38	<u>L25</u>
<u>L24</u>	l22 and ((second near3 (air or gas)) or idle or idling or purg\$3)	75	<u>L24</u>
<u>L23</u>	l22 and ((second near3 (air or gas)) or idle or idling)	63	<u>L23</u>
<u>L22</u>	L21 and ((wafer or semiconductor) same etch\$3)	106	<u>L22</u>
<u>L21</u>	l19 and l20	223	<u>L21</u>
<u>L20</u>	rf near4 (cool\$3)	1608	<u>L20</u>
<u>L19</u>	rf same (cooling near3 gas\$2)	731	<u>L19</u>
<u>L18</u>	rf same (cda or (clean adj dry adj air) or (compressed adj dry adj air))	59	<u>L18</u>
<u>L17</u>	l10 and (chang\$3 near3 temperature)	48	<u>L17</u>
<u>L16</u>	L9 and (second near3 supply)	98	<u>L16</u>
<u>L15</u>	l10 and (second near2 air)	109	<u>L15</u>
<u>L14</u>	l10 and (temperature near4 control\$4)	109	<u>L14</u>
<u>L13</u>	l10 and (dome\$1)	2	<u>L13</u>
<u>L12</u>	l10 and plasma	6	<u>L12</u>
<u>L11</u>	L9 and (second near2 cda)	1	<u>L11</u>
<u>L10</u>	L9 and (second near2 air)	109	<u>L10</u>
<u>L9</u>	air same (control\$3 near4 temperature) same (wafer or semiconductor)	1668	<u>L9</u>
<u>L8</u>	air same (control\$3 near4 temperature)	103801	<u>L8</u>
<u>L7</u>	cda same (control\$3 near4 temperature)	11	<u>L7</u>
<i>DB=PGPB; PLUR=YES; OP=ADJ</i>			
<u>L6</u>	20050233479 and (clean adj dry adj air)	0	<u>L6</u>
<u>L5</u>	20050233479 and (compressed adj dry adj air)	0	<u>L5</u>
<i>DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>			
<u>L4</u>	cda same (wafer or semiconductor) same (chamber or reactor or rf)	22	<u>L4</u>
<u>L3</u>	cda same (wafer same plasma)	2	<u>L3</u>
<u>L2</u>	cda same controller	107	<u>L2</u>
<i>DB=PGPB; PLUR=YES; OP=ADJ</i>			
<u>L1</u>	20050233479 and cda	1	<u>L1</u>

END OF SEARCH HISTORY